

10/695,528

Sheet 1 of 1

U.S. Department of Commerce, Patent and Trademark Office				Attorney Docket No.: NEC0254US		Serial No.: Unassigned	
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use several sheets if necessary)				Applicant(s): John W. Jacobs and Elizabeth A. Dauch			
► EXPRESS MAIL LABEL NO.: EV 304 737 528 US ◀				Filing Date: Concurrently herewith		Group Art Unit: Unassigned	
U.S. Patent Documents							
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
LT	AA	4,901,194	Feb. 13, 1990	Steinman et al.	361	213	Dec. 29, 1988
LT	AB	6,077,762	Jun. 20, 2000	Victor C. Liang et al.	438	593	Dec. 22, 1997
LT	AC	6,153,531	Nov. 28, 2000	Subhas Bothra, et al.	438	745	Dec. 22, 1997
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
	AK						
Foreign Patent Documents							
		Document	Date	Country	Class	Subclass	Translation Yes No
	AL						
	AM						
	AN						
	AO						
	AP						
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)							
LT	AQ	Bothra, S., H. Sur and V. Liang, "A New Failure Mechanism by Corrosion of Tungsten in a Tungsten Plug Process," Technology Development, VLSI Technology, Inc., San Jose, California, 95131; 1998 IEEE.					
	AR						
	AS						
Examiner: <i>Markman</i>				Date Considered: 6/28/05			
*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.							

U.S. Department of Commerce, Patent and Trademark Office					Attorney Docket No.: <b>NEC0254US</b>		Application No.: 10/695,528	
<b>INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b> (Use several sheets if necessary)					Applicant(s): John W. Jacobs		Confirmation No.: 6404	
					Filing Date: October 28, 2003		Group Art Unit: 2891	
<b>U.S. Patent Documents</b>								
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
LT	AA	5,336,371	Aug. 9, 1994	Chung et al.	156	659.1		
	AB	6,077,762	Jun. 20, 2000	Liang et al.	438	593		
	AC	6,153,531	Nov. 28, 2000	Bothra et al.	438	745		
	AD	6,277,742 B1	Aug. 21, 2001	Wang et al.	438	672		
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	AF	6,358,329 B1	Mar. 19, 2002	Muranaka et al.	134	26		
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LT	AH	6,851,873 B2	Feb. 8, 2005	Muraoka et al.	396	611		
	AI							
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<b>Patent Application Publication</b>								
		Publication Number	Pub. Date	Name	Class	Subclass	Filing Date If Appropriate	
LT	AK	2002 0036001 A1	Mar. 28, 2002	Ise et al.	134	1.3		
LT	AL	2002 0053355 A1	May 9, 2002	Kamikawa et al.	134	30		
LT	AM	2003 0006513 A1	Jan. 9, 2003	Gotoh et al.	261	122.1		
	AN							
<b>Foreign Patent Documents</b>								
							Translation	
		Document	Date	Country	Class	Subclass	Yes	No
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<b>OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)</b>								
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